



Plasma Enhanced Chemical Vapor Deposition (PECVD)

Plasmalab 100

Manufacturer: Oxford Instruments

Depositions:

- Silicon Nitride, Silicon Oxide, Silicon Oxynitride and amorphous silicon

Types of substrates:

- 2", 4", 8", small pieces of wafers – Si, glass, quartz

Substrate Temperature:

- Room temp to 380 Degree C

Process gases used

- SiH_4 , N_2O , CF_4 , N_2 , He, Ar, NH_3 , H_2

